

## SUPPORTING INFORMATION

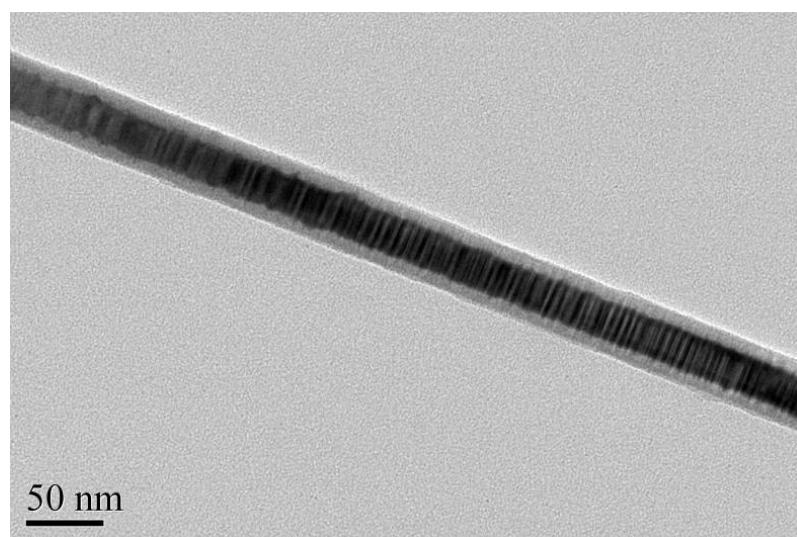
### **High performance rigid and flexible visible-light photodetectors based on aligned X(In, Ga)P nanowire arrays**

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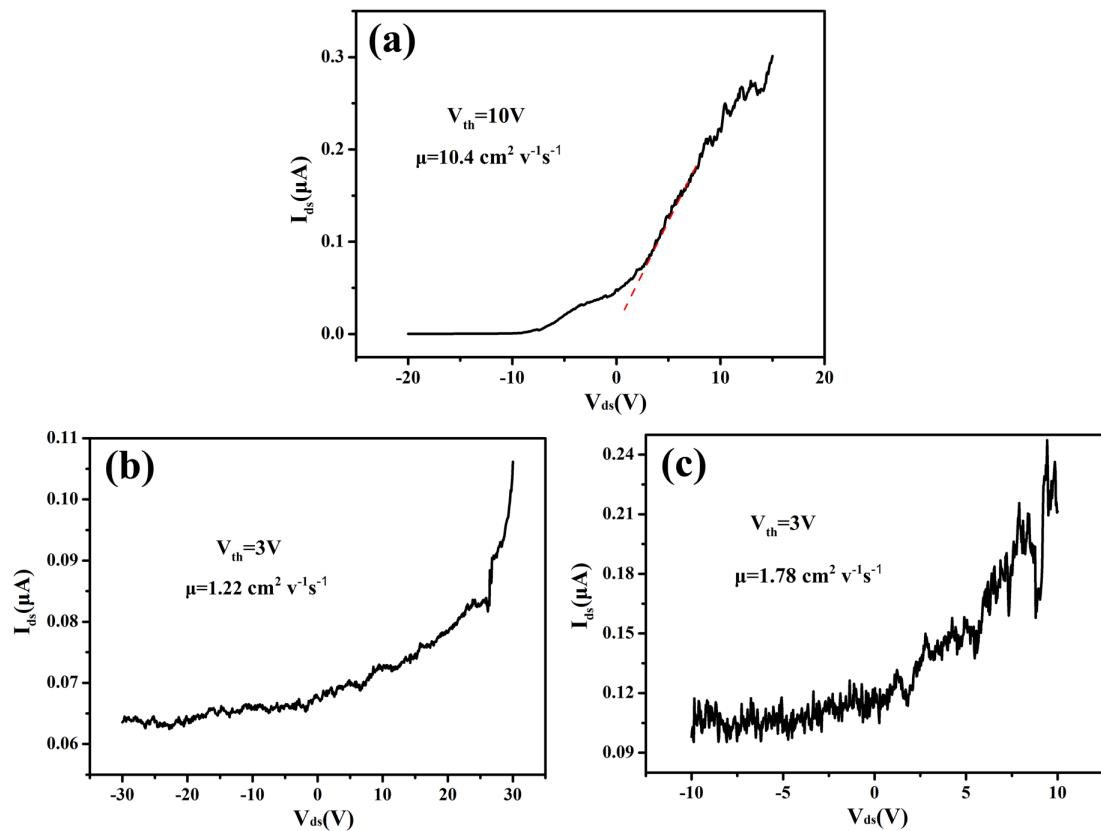
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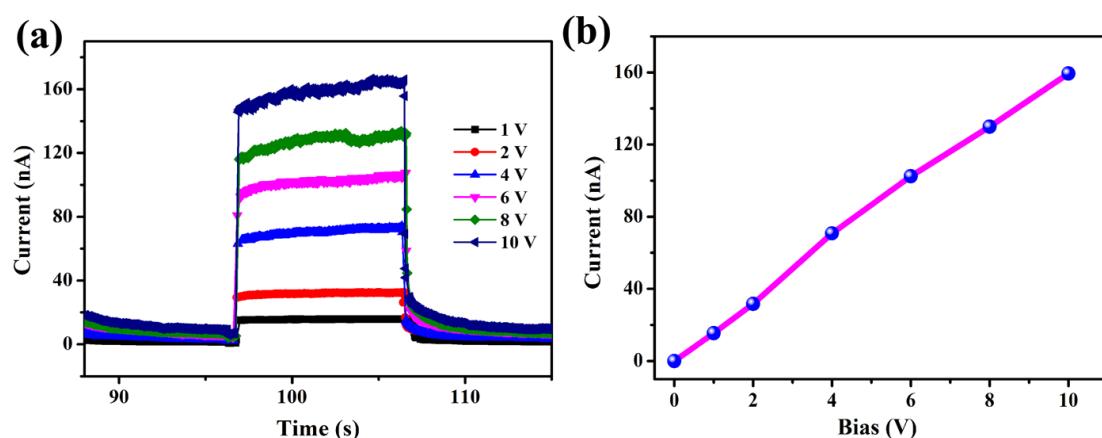
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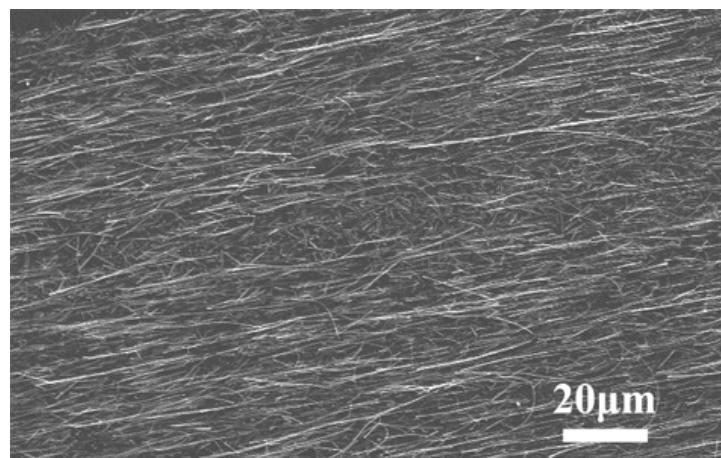
**Figure S1** High-magnification TEM images of the InP NWs.



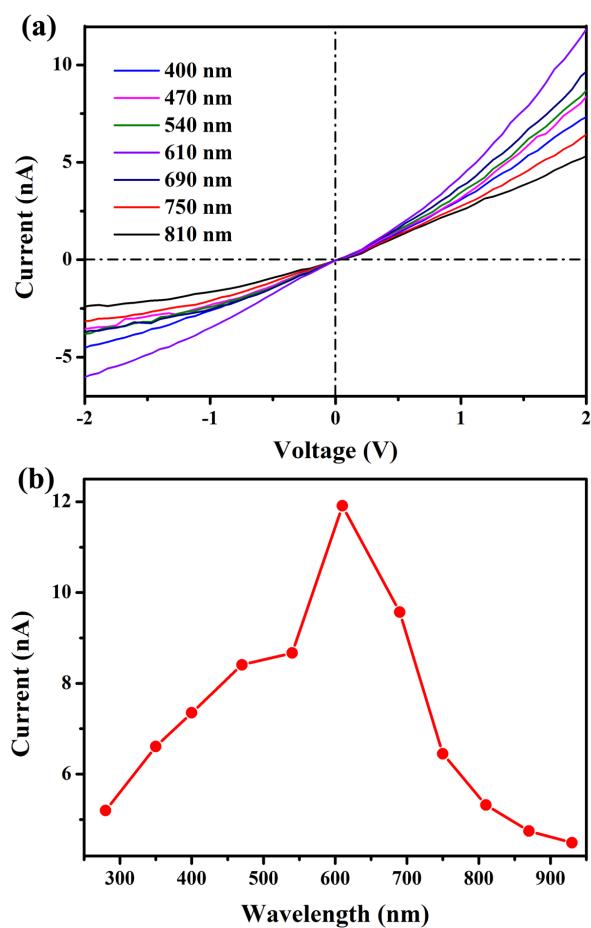
**Figure S2** Effective mobilities based on three single InP devices, The mobility range on single devices is about  $1\sim10 \text{ cm}^2 \text{ V}^{-1} \text{s}^{-1}$ .



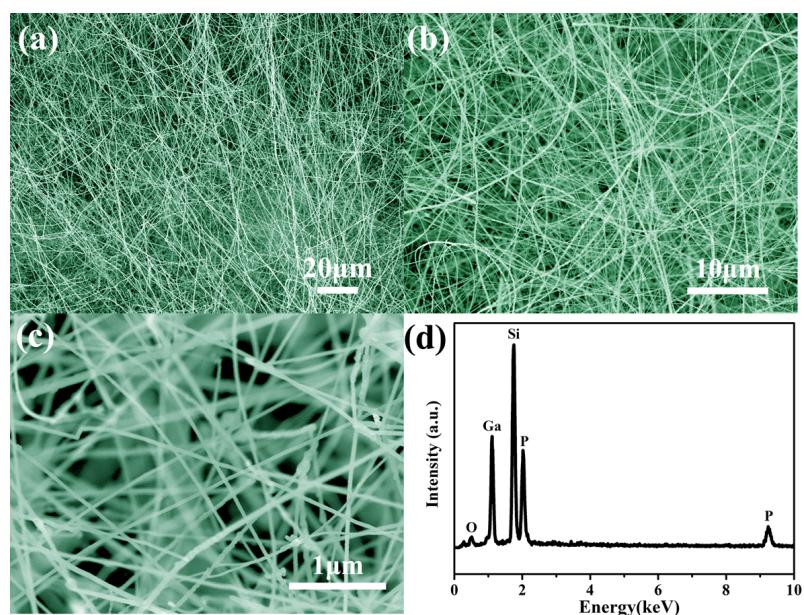
**Figure S3** Photoreponse properties of single InP NW PD on rigid  $\text{SiO}_2/\text{Si}$  substrate.  
(a) Photocurrent versus time plots of the device using by red light (633 nm) at an intensity of  $3.15\text{mW/cm}^2$  at different biases. (b) Photocurrent versus voltage plots for the single NW device in the dark and at light intensity of  $3.15\text{mW/cm}^2$ .



**Figure S4** SEM image of aligned InP NW arrays on  $\text{SiO}_2$  coated Si substrates



**Figure S5** Current-voltage curves of the device illuminated by lights with different wavelengths. The light intensity was kept constant at  $0.9 \text{ mW/cm}^2$ .



**Figure S6** (a-c) low-magnification and high-magnification SEM images of the as-synthesized GaP nanowires. (d) EDS spectrum of a single GaP nanowire.